

ABSTRACT OF THE DISCLOSURE

An electron beam exposure apparatus for exposing a wafer by an electron beam, including: an electron beam generating section
5 for generating the electron beam; a deflector for deflecting the electron beam; a deflection control section for outputting a deflection control signal for causing the deflector to deflect the electron beam; and a control signal storage section for storing a value of the deflection control signal output from the deflection
10 control section. The control signal storage section and the deflector may be monolithically integrated on a semiconductor substrate.